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- 94) - Electron energy distributions in a magnetized inductively coupled plasma
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- 93) - Ground state bromine atom density measurements by two-photon absorption laser-induced fluorescence
N. Sirse, M. Foucher, P. Chabert and J-P Booth
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- 92) - A review on ion-ion plasmas created in weakly magnetized electronegative plasmas
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- 91) – What is the size of a floating sheath?
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- 90) - Electron heating in capacitively coupled plasmas revisited
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- 89) - Particle-in-cell and global simulations of α to γ transition in atmospheric pressure Penning-dominated capacitive discharges
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- 88) - A radio-frequency sheath model for complex waveforms
M M Turner and P Chabert
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- 87) - Equivalence of the hard-wall and kinetic-fluid models of collisionless electron heating in capacitively coupled discharges
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- 84) - Electrical characteristics of micro-hollow cathode discharges
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- 83) - Reduced electron temperature in a magnetized inductively-coupled plasma with internal coil
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- 82) - Chlorine atom densities in the $(3p^5)^2P_{1/2}$ excited spin-orbit state measured by two-photon absorption laser-induced fluorescence in a chlorine inductively-coupled plasma
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- 81) - Langmuir probe analysis of highly electronegative plasmas
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- 80) - Particle-in-cell simulation of an electronegative plasma under direct current bias studied in a large range of electronegativity
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- 79) - Secondary electron induced asymmetry in capacitively coupled plasmas
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- 74) - Dynamics of neutral gas depletion investigated by time- and space-resolved measurement of xenon atom ground state density

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